



# Medium-Range Order of Metallic Glass Thin Films

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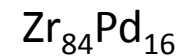
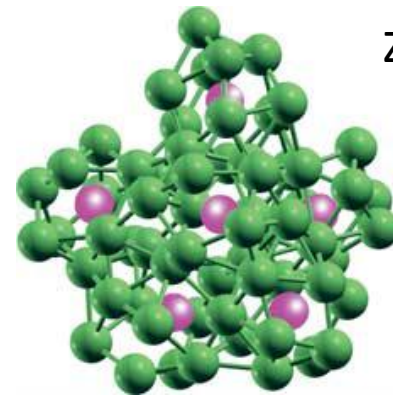
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# Findings of this work

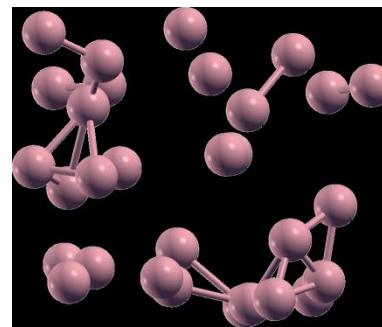
- Medium range order in metallic glass thin films is lower than the bulk materials, for both the marginal glass  $\text{Al}_{90}\text{Tb}_{10}$  and the bulk metallic glass  $\text{Zr}_{53}\text{Cu}_{29}\text{Al}_{12}\text{Ni}_6$ .
- In ZrCuAlNi glass, annealing induces short and medium range structural at temperatures much lower than  $T_g$ . Annealing over time also widens compositional segregation of Zr and Cu.

# Introduction: formation of medium range order in metallic glass

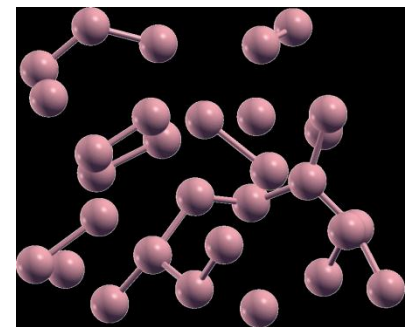
- MROs result from connection of short-range-order clusters.
- To study how MROs change with MG cooling condition, our experiment compares MROs in liquid-quenched bulk MG with vapor deposited MG thin film.



H. W. Sheng et al, NATURE **439**  
26, 2006



1800 K



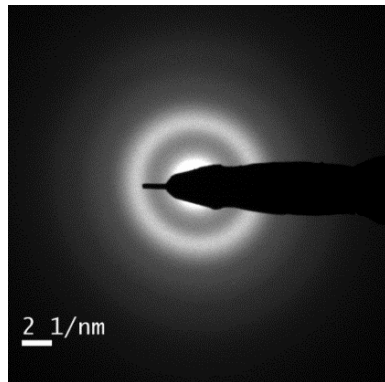
300 K



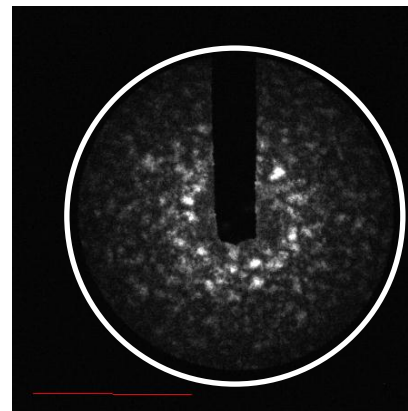
# Experiment: fluctuation electron microscopy

- MRO: three or four body correlations in atomic structures depicted in  $\langle I^2 \rangle$ .

$$V(k) = \frac{\langle I(k, \mathbf{r})^2 \rangle_{\mathbf{r}}}{\langle I(k, \mathbf{r}) \rangle_{\mathbf{r}}^2} - 1$$



Broad electron beam diffraction



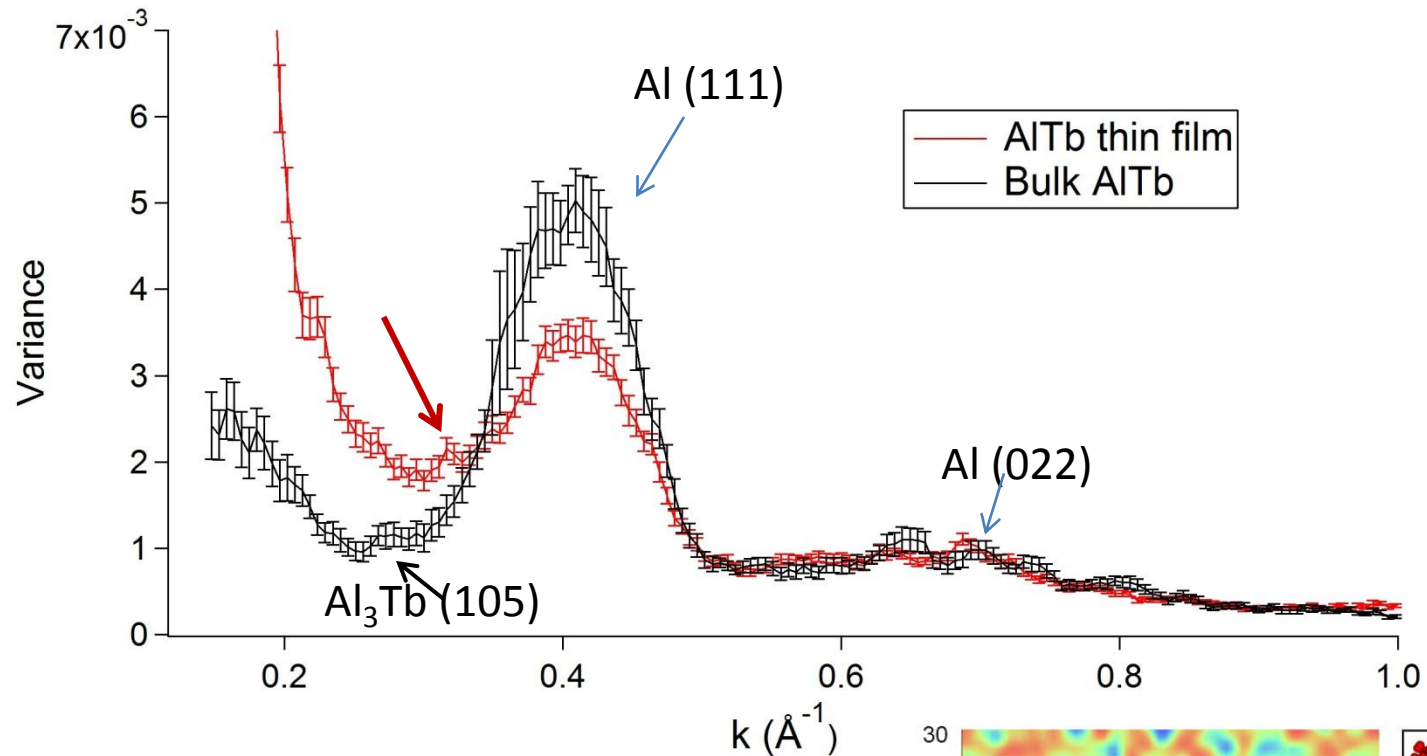
Nano beam diffraction

Average  $I$   
and  $I^2$  over  
the same  
 $k$ .

M M J Treacy et al., Rep. Prog. Phys. **68** (2005) 2899–2944

“Fluctuation Electron Microscopy” Jinwoo Hwang and P. M. Voyles, in *Characterization of Materials*, E. N. Kaufmann, ed., Wiley (2012).

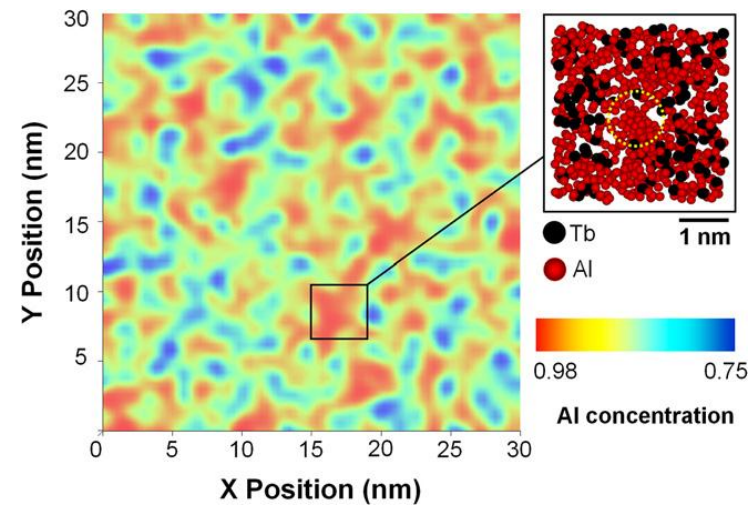
# Metallic glass I: AlTb



MG samples: bulk Al<sub>90</sub>Tb<sub>10</sub>, melt-spinning; Al<sub>90</sub>Tb<sub>10</sub> film, sputtering.  
FEM conditions: 2 nm electron beam, 1000 sample positions.

Bulk Al<sub>90</sub>Tb<sub>10</sub>  
atom probe  
data

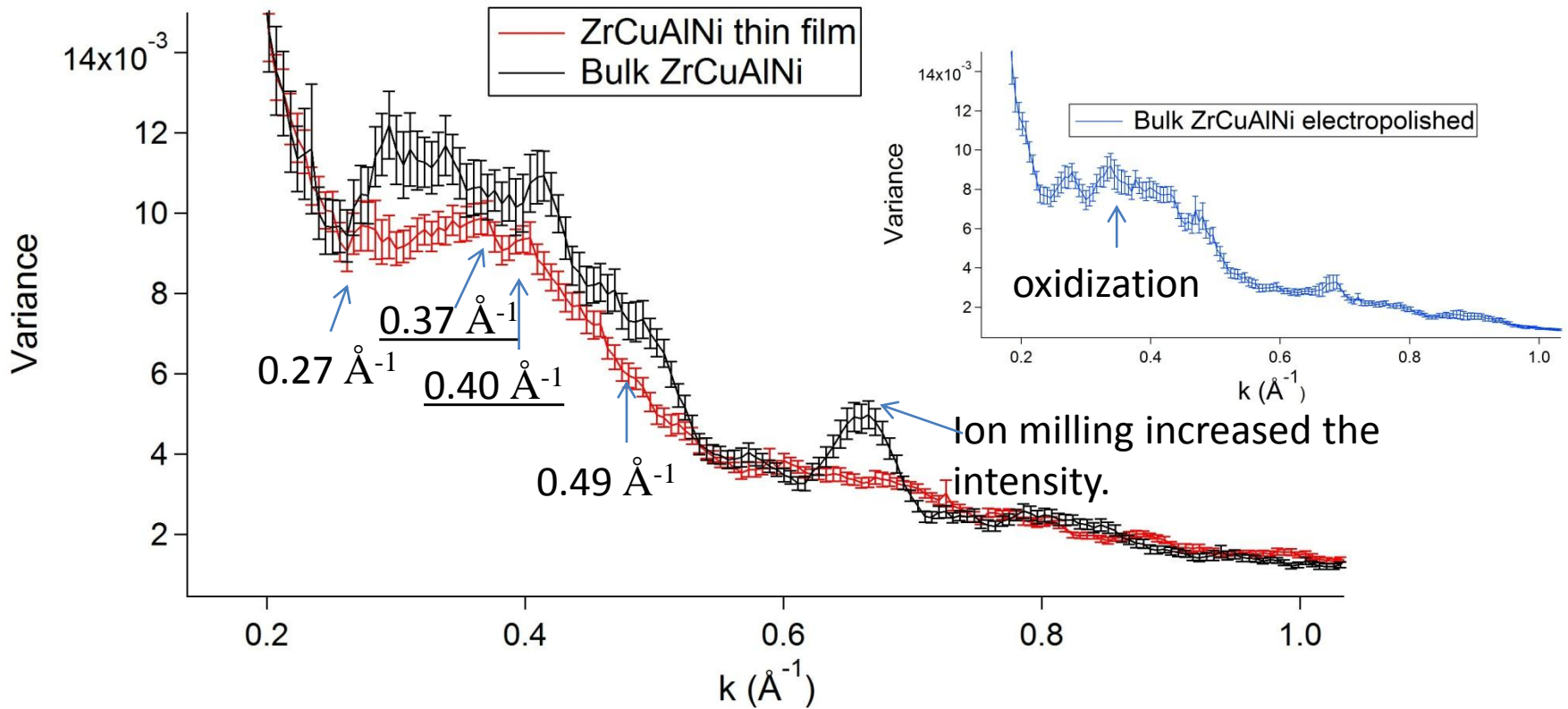
Y.E. Kalay et al. / Acta  
Materialia **60** (2012)  
994–1003



# MRO in AlTb

- Lower variance intensity at the major peak suggests lower level of Al-like MROs or more homogeneous glass are present in the thin film.
- The pre-peak (indicated by arrows) shifts to higher  $k$ .
- Variance peaks at high  $k$  ( $0.6-0.8 \text{ \AA}^{-1}$ ,  $k=1/d$ ) is lower in the thin film. As smaller  $d$  is more sensitive to disorder, this reflects a more disordered structure.
- **Increasing cooling rate appears to reduce MROs and increase intermixing of Al and Tb.**

# Metallic glass II: ZrCuAlNi



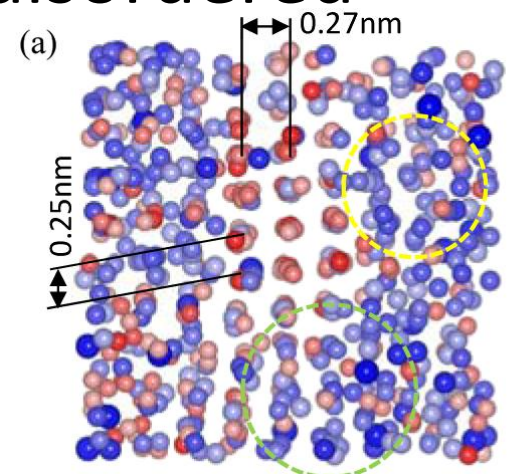
Zr<sub>53</sub>Cu<sub>29</sub>Al<sub>12</sub>Ni<sub>6</sub>, 20 nm thin film was sputtered on 5 nm thick amorphous Si. Bulk ingot was produced by arc melting. Ion milling: 4 kV Ar<sup>+</sup>.

# MRO in ZrCuAlNi

- A variety of MROs exist in both thin film and bulk ZrCuAlNi. The difference in MROs could be rotational symmetry or others<sup>1</sup>.
- Thin film is more homogeneous than bulk material. The missing of MRO peak in thin film at  $\sim 0.68 \text{ \AA}^{-1}$  also reflects a more disordered structure.

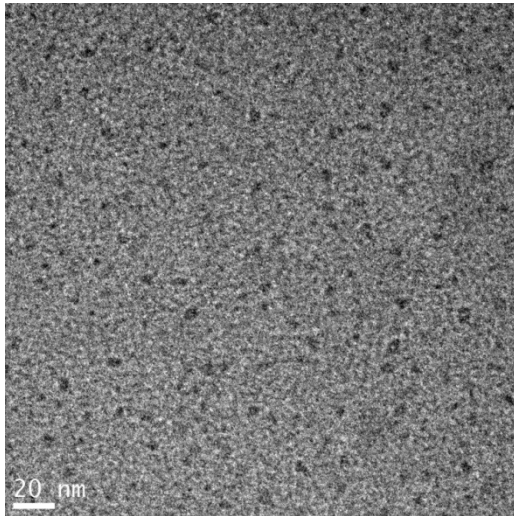
1. Jinwoo Hwang et al, PRL **108**, 195505 (2012)

This paper reports  $0.37 \text{ \AA}^{-1}$  and  $0.40 \text{ \AA}^{-1}$  MROs in  $\text{Zr}_{50}\text{Cu}_{45}\text{Al}_5$  are icosahedral-like or crystal-like MROs, respectively.

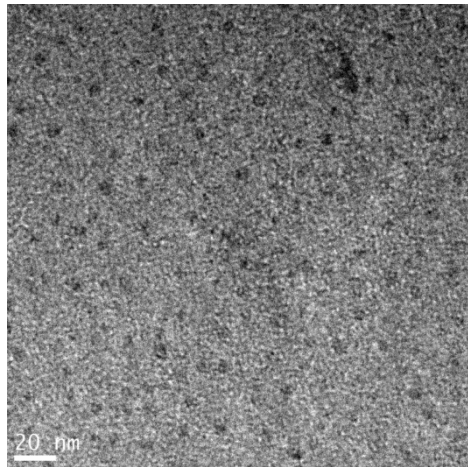




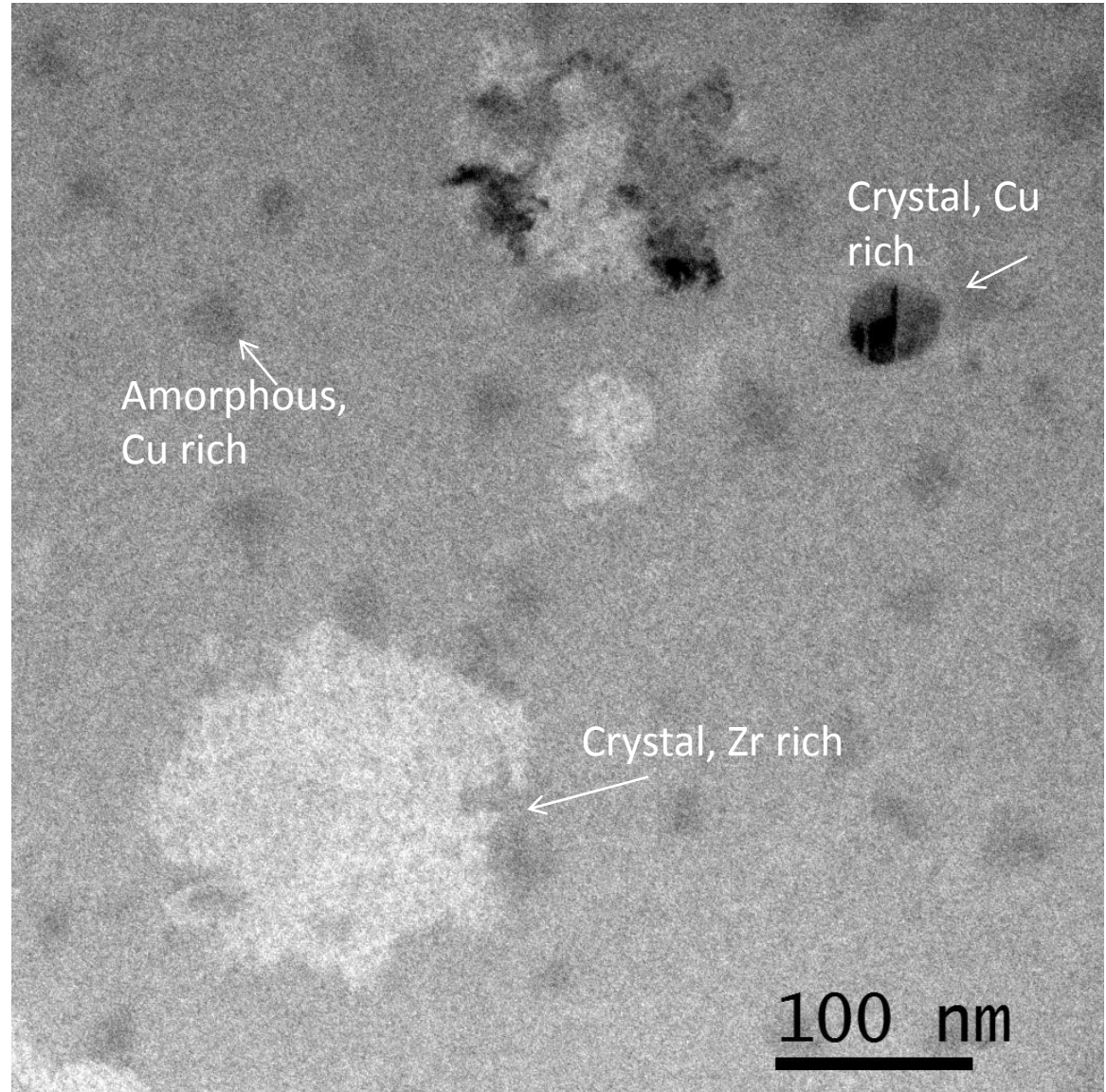
# In-situ annealing of ZrCuAlNi thin film



20 nm  
TEM bright field image, R.T.  
as deposited.

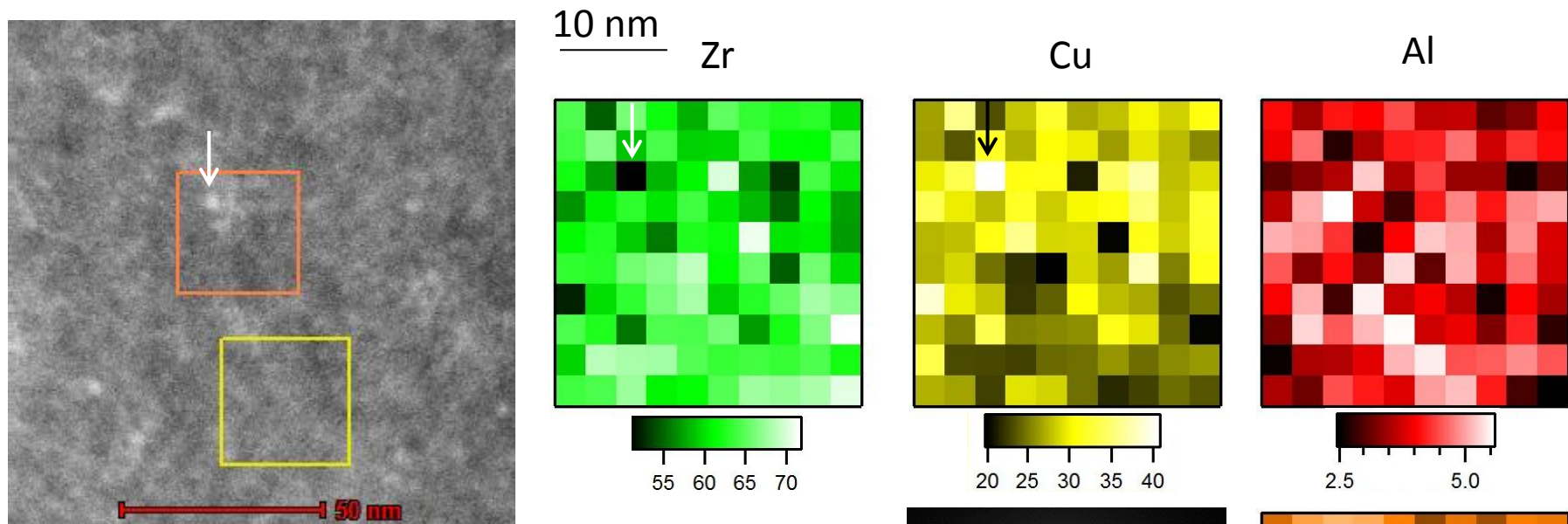


20 nm  
R.T. after heating up to **405 °C** (2  
hours 10 minutes at 405 °C)



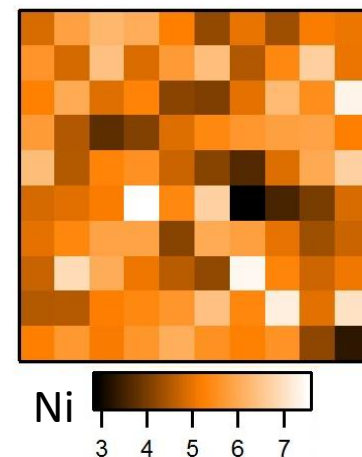
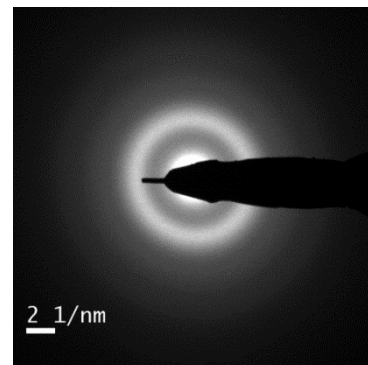
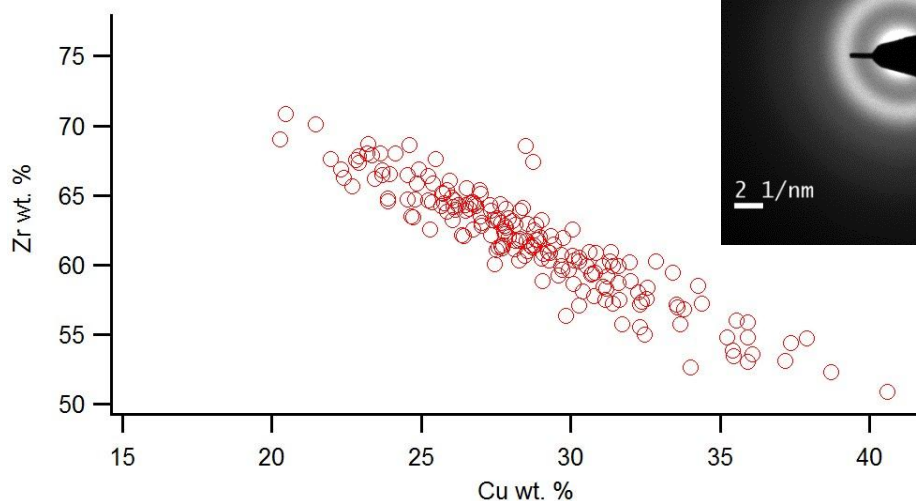
R.T. after heating up to **493 °C** (1 hours 29 minutes at  
493 °C)

# Chemical analysis of 150 °C annealed sample

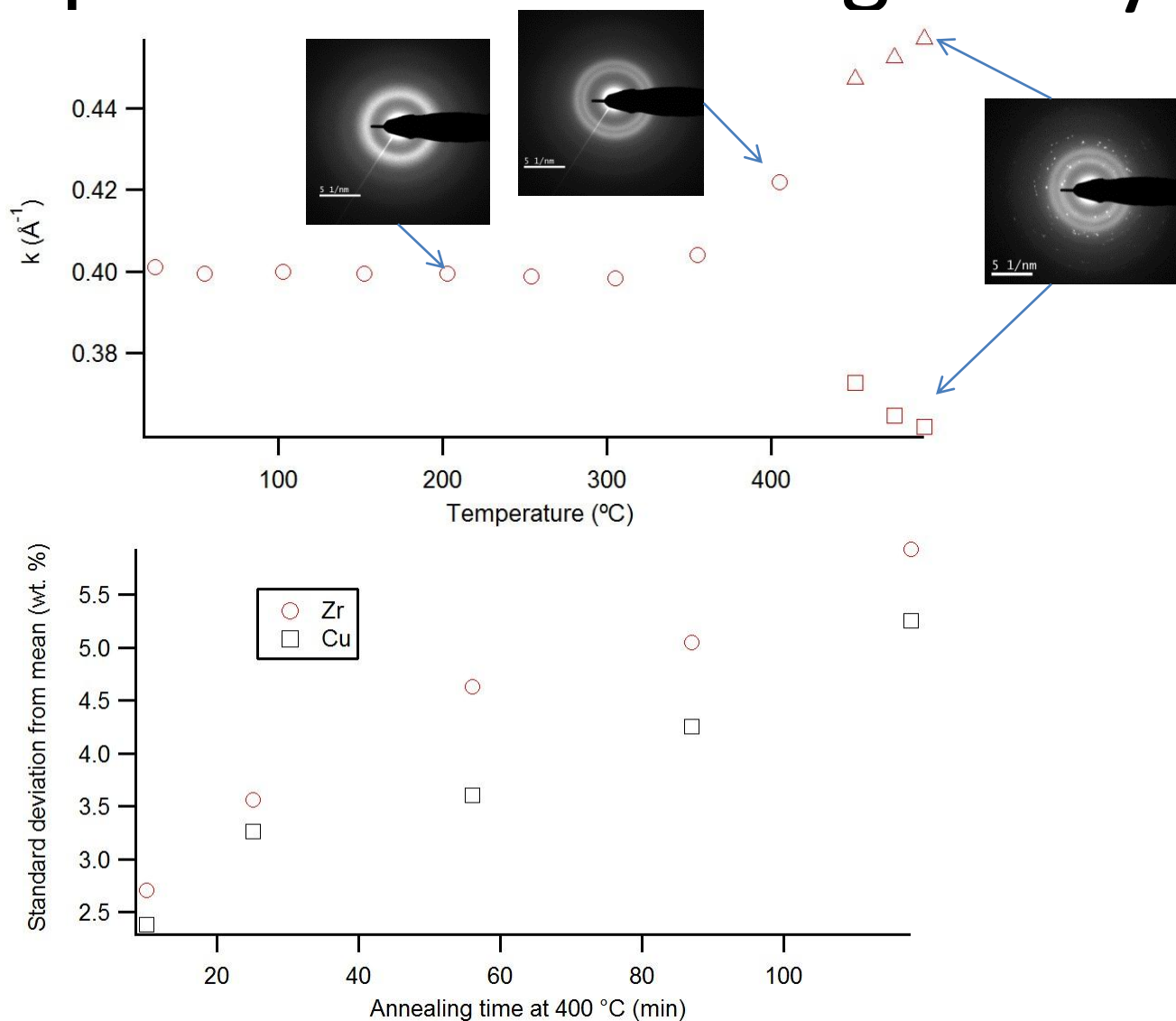


HAADF image, R.T.  
after heating at  
150 °C for 11 min.

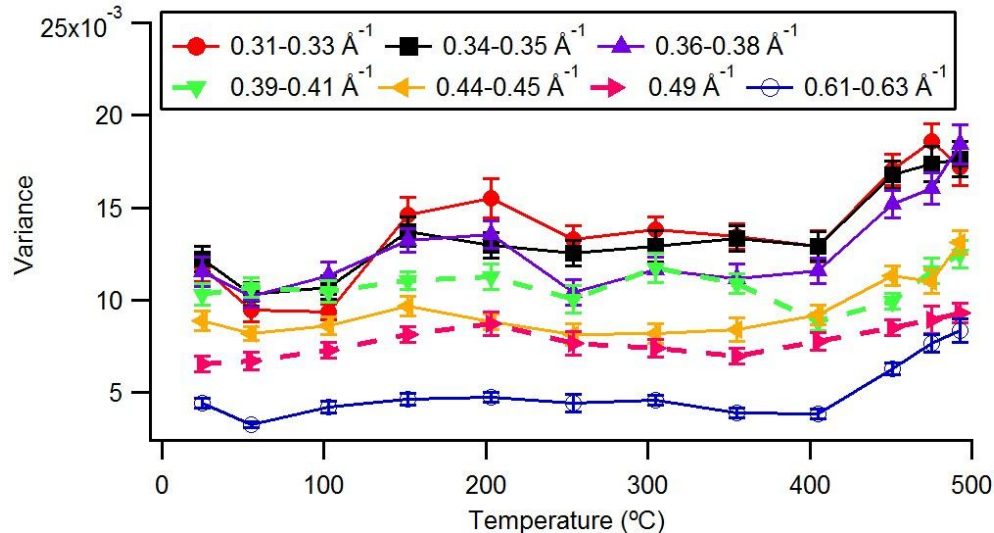
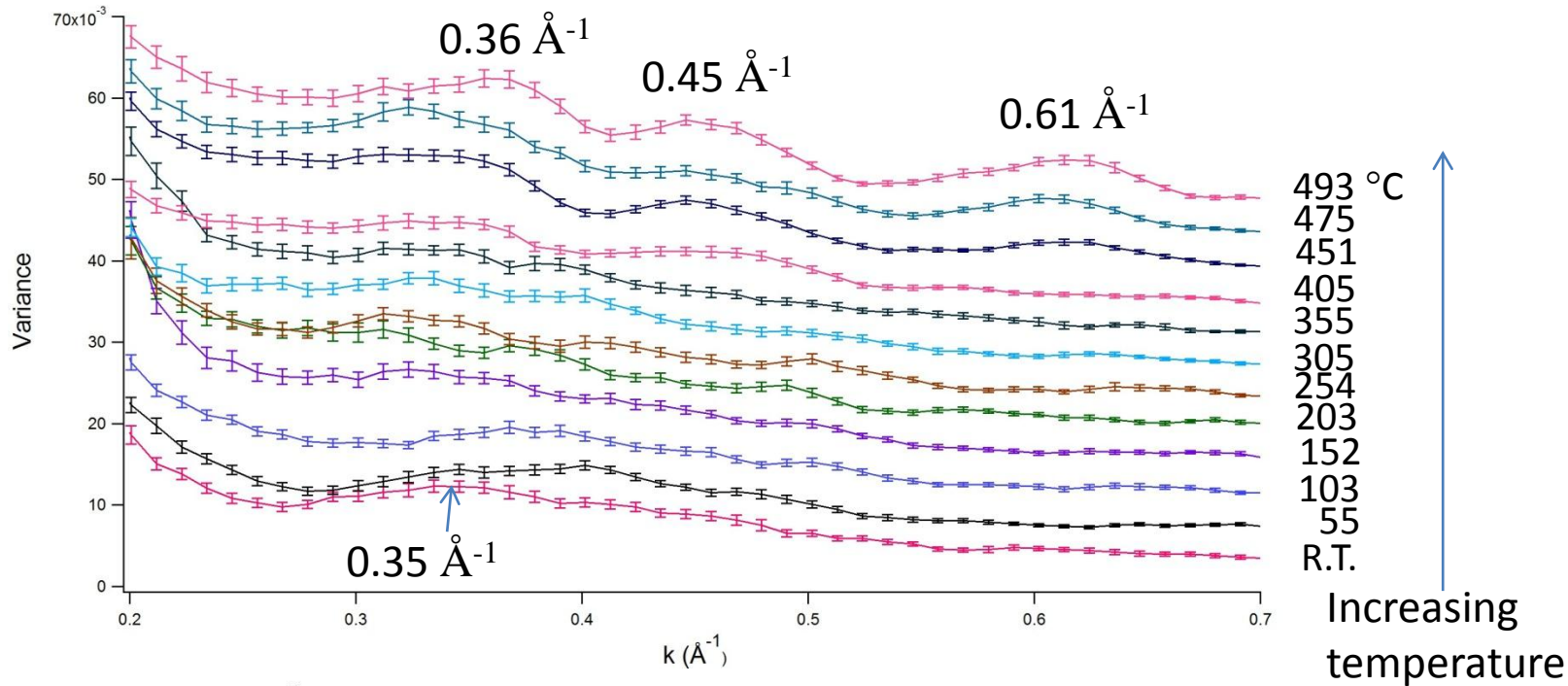
Nominal  
composition (wt.  
%): Zr 66, Cu 25, Al  
4, Ni 5.



# Short range order and compositional inhomogeneity



# Annealing effect to ZrCuAlNi thin film MROs



Variance may increase  
(e.g., 0.36 Å<sup>-1</sup>) or  
decrease (e.g., 0.40 Å<sup>-1</sup>)  
at higher annealing  
temperature.

# Conclusion

- Thin film  $\text{Al}_{90}\text{Tb}_{10}$  and  $\text{Zr}_{53}\text{Cu}_{29}\text{Al}_{12}\text{Ni}_6$  metallic glasses have less medium-range order than bulk materials.
- $\text{ZrCuAlNi}$  thin film exhibits compositional inhomogeneity. Cu-rich and Zr-rich clusters are present. No phases (at certain compositions) are identified.
- Change of short range order/ atom spacing takes place at about 350 °C.
- Compositional inhomogeneity increases with annealing time at 400 °C.
- Medium range order increases as annealing temperature approaches above 400 °C.